

# 제22회 한국반도체학술대회

2015년 2월 10일(화) - 12일(목), 인천 송도컨벤시아

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## G. Device & Process Modeling, Simulation and Reliability 분과

Room C  
1F / 106호

2015년 2월 11일(수) 09:00-10:30

[WC1-G] Device Modeling and Simulation

좌장: 이재규 (삼성전자), 조인욱 (SK Hynix Inc.)

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| WC1-G-1 | 09:00-09:15 | <b>A Newly-Proposed Vacuum-Channel Transistor</b><br>In Jun Park and Changhwan Shin<br>School of Electrical and Computer Engineering, University of Seoul  |
| WC1-G-2 | 09:15-09:30 | <b>DFT-NEGF Simulation of Si Nanowire Transistors using Reduced-Sized Hamiltonian</b><br>Woo Jin Jeong, Jaehyun Lee, and Mincheol Shin<br>Department of Electrical Engineering, KAIST  |
| WC1-G-3 | 09:30-09:45 | <b>Multiple Negative Differential Resistance Device by using the Ambipolar Behavior of TFET with Fast Switching Characteristics</b><br>Jaewon Jung, Sunhae Shin, Esan Jang, and Kyung Rok Kim<br>School of Electrical and Computer Engineering, Ulsan National Institute of Science and Technology |
| WC1-G-4 | 09:45-10:00 | <b>Analysis of Stress Effect on (110)-oriented Single Gate SOI nMOSFETs using Silicon-Thickness-Dependent Deformation Potential</b><br>Sujin Choi, Wookyung Sun, Injae Lee, and Hyungsoon Shin<br>Department of Electronics Engineering, Ewha Womans University                                    |
| WC1-G-5 | 10:00-10:15 | <b>Effects of Ferroelectric Thickness on Negative Capacitance FET Inverters</b><br>Junbeom Seo, Jaehyun Lee, and Mincheol Shin<br>Department of Electrical Engineering, KAIST  |
| WC1-G-6 | 10:15-10:30 | <b>Design and Analysis of Gate-recessed AlGaIn/GaN Fin-type Field-Effect Transistor</b><br>Young In Jang, Jae Hwa Seo, Young Jun Yoon, Hye Rim Eun, Ra Hee Kwon, Jin Su Kim, Jung-Hee Lee, and In Man Kang<br>School of Electronics Engineering, Kyungpook National University                     |